Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

Claims 1 - 15: Cancelled

16. (New) A method of drying substrates after a wet treatment thereof in treatment liquid, including the steps of:

forming a gas mixture that comprises a carrier gas and an active substituent, and that reduces the surface tension of the treatment liquid, by conveying the carrier gas through a liquid of the active substituent;

actively controlling a concentration of the active substituent in the gas mixture in an open or closed loop manner;

actively controlling a temperature of the liquid of the active substituent to a predetermined temperature in an open or closed loop manner;

applying the gas mixture to the treatment liquid; and

moving the substrates out of the treatment liquid by generating a relative movement between the substrates and the treatment liquid.

- 17. (New) A method according to claim 16, wherein the gas mixture is formed by mixing essentially pure carrier gas and a mixture of carrier gas and the active substituent.
- 18. (New) A method according to claim 16, wherein the temperature of the liquid of the active substituent is kept essentially constant.
- 19. (New) A method according to claim 16, wherein the temperature of the liquid of the active substituent is altered in a controlled manner throughout a drying process.
 - 20. (New) A method according to claim 19, wherein the concentration of the active

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substituent in the gas mixture is measured, and wherein the temperature of the liquid of the

active substituent is adjusted as a function of the measured concentration.

21. (New) A method according to claim 16, wherein a flow rate of the carrier gas is

controlled in an open or closed loop manner.

22. (New) A method according to claim 21, wherein the flow rate of the carrier gas is

altered throughout a drying process.

23. (New) A method according to claim 21, wherein the concentration of the active

substituent in the gas mixture is measured, and the flow rate of the carrier gas is adjusted as a

function of the measured concentration.

24. (New) A method according to claim 16, wherein the gas mixture is at least

partially formed by introducing a predetermined quantity of the carrier gas and a predetermined

quantity of a liquid of the active substituent into an evaporator.

25. (New) A method according to claim 24, wherein the concentration of the active

substituent in the gas mixture is measured downstream of the evaporator, and wherein a flow

rate of at least one of the carrier gas and the liquid of the active substituent is adjusted as a

function of the measured concentration in order to obtain a predetermined concentration.

26. (New) A method according claim 16, wherein the concentration of the active

substituent in the gas mixture is altered as a function of a position of the substrates relative to a

surface of the treatment liquid.

27. (New) A method according to claim 26, wherein the concentration of the active

substituent in the gas mixture is increased as a cross-sectional surface between the substrates

and the treatment liquid increases, and is decreased as the cross-sectional surface is

decreased.

28. (New) A method according to claim 16, wherein the active substituent is

isopropyl alcohol (IPA), and wherein the average IPA concentration in the gas mixture is kept

below 15% of a lower explosion level (LEL).

- 29. (New) A method according to claim 28, wherein the average IPA concentration in the gas mixture is kept below 10% of the lower explosion level (LEL).
- 30. (New) A method according to claim 28, wherein the average IPA concentration in the gas mixture is kept between 3 and 10% of the lower explosion level (LEL).